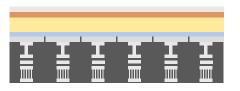


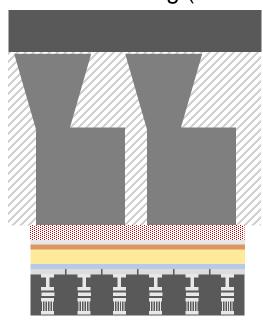
1. ROIC Fabrication



**2.** Monolithic integration of PePD



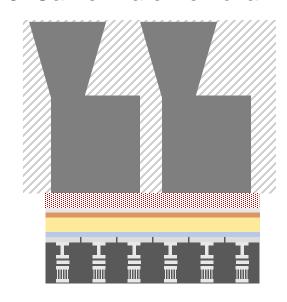
**4.** Direct wafer bonding via SiO<sub>2</sub>/SiCN interlayer and thermal annealing (>250°C)



**3.** Waveguide matrix on carrier wafer



5. Carrier wafer removal



(b)